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Patent

Attorney Docket No. 005950-844

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of
Shenggao Liu et al.

Application No.: 10/764,407

Filing Date: January 23, 2004

Title: PHOTORESIST COMPOSITIONS COMPRISING DIAMONDROID DERIVATIVES

Group Art Unit: 1755

Examiner:

Confirmation No.: 9511

FIRST
INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Enclosed is a FIRST Information Disclosure Statement and accompanying form PTO-1449 for the above-identified patent application.

- ☒ No additional fee for submission of an IDS is required.
- ☐ The fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) is also enclosed.
- ☐ A statement under 37 C.F.R. § 1.97(e) is also enclosed.
- ☐ A statement under 37 C.F.R. § 1.97(e), and the fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) are also enclosed.
- ☐ Charge _____ to Deposit Account No. 02-4800 for the fee due.
- ☐ A check in the amount of _____ is enclosed for the fee due.
- ☐ Charge _____ to credit card. Form PTO-2038 is attached.

The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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By

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Registration No. 43,014

Date: 10-14-04

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Application No.: 10/764,407

Filed: January 23, 2004

For: PHOTORESIST COMPOSITIONS
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DERIVATIVES

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Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, the accompanying information is being submitted in accordance with 37 C.F.R. §§ 1.97 and 1.98.

Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited is enclosed. However, copies of the listed U.S. patents and U.S. patent application publications are not enclosed since it is no longer required according to the July 11, 2003 waiver of the requirement for copies of cited U.S. patents and U.S. patent application publications in national patent applications filed after June 30, 2003 and international applications entering the national stage under 35 U.S.C. § 371 after June 30, 2003.

The documents are being submitted within three (3) months of the filing or entry of the national stage of this application or before the first Office Action on the merits, whichever is later. Since these documents are being filed within the time period set forth in 37 C.F.R. § 1.97(b), no fee or statement is required.

To assist the Examiner, the document is / documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned.

Respectfully submitted,

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Date 10-14-04

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FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Complete if Known

Application Number	10/764,407
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First Named Inventor	Shenggao Liu et al.
Examiner Name	
Attorney Docket Number	005950-844

Sheet

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Examiner
SignatureDate
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 2 of 3

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Application Number	10/764,407
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Substitute for form 1449A/PTO & 1449B/PTO			Complete if Known		
FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(use as many sheets as necessary)</small>			Application Number	10/764,407	
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			First Named Inventor	Shenggao Liu et al.	
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Sheet	3	of	3		

FOREIGN PATENT DOCUMENTS											
Examiner Initials	Document Number	Kind Code (if known)	Country	Date of Publication (MM-DD-YYYY)	STATUS						
					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited in Spec
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Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
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Examiner Signature	Date Considered
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